

Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application:

Listing of Claims:

1. (Currently Amended) A plasma CVD apparatus comprising:
 - a vacuum chamber;
 - an exhaust means for exhausting the gas from the vacuum chamber to an outside;
 - an electrode for supplying an electric energy inside the vacuum chamber;
 - a supporting means for supporting a substrate opposing the electrode wherein said substrate is moved in a first direction through said chamber;
 - an introducing port for gas, located located between the electrode and the substrate wherein said gas is introduced into said chamber in a direction parallel with said first direction so that a flow of said gas is rectified in a direction away from a film formation surface of the substrate;
 - wherein a plurality of openings are located on a surface of the electrode opposing the substrate,
 - wherein the gas is exhausted from the plurality of openings to the outside of the vacuum chamber.
2. (Previously Presented) An apparatus according to claim 1, further comprising:
 - a transporting means for transporting continuously a flexible the substrate in said first direction.
3. (Original) An apparatus according to claim 1, wherein each of the plurality of openings is circular,
 - wherein the plurality of openings are located on the surface of the electrode at constant intervals.

4. (Original) An apparatus according to claim 1, wherein the electrode is a mesh-like plate.

5. (Cancelled)

6. (Previously Presented) An apparatus according to claim 1 further comprising:
a second electrode opposing the first electrode for supplying the electric energy inside the vacuum chamber.

7. (Previously Presented) An apparatus according to claim 6,
wherein the substrate is supported between the first and second electrodes by the supporting means.

8. (Previously Presented) An apparatus according to claim 2,
wherein the transporting means includes at least one selected from the group consisting of an unwinding roll and a winding roll.

9. (Previously Presented) The apparatus according to claim 1 wherein said substrate is located horizontally and said has a substrate surface downward that is downwardly opposed to the electrode.

10. (Currently Amended) An apparatus comprising:
a chamber;
a first electrode in the chamber;
a second electrode in the chamber;
a substrate holder to hold a substrate between the first and second electrode wherein said substrate is moved in a first direction through said chamber;

at least one gas inlet port to introduce a gas to a space between the substrate and the second electrode wherein said gas is introduced in a direction parallel to said first direction so that a flow of said gas is rectified in a direction away from a film formation surface of the substrate; and

a plurality of gas exhaust ports provided in said second electrode through which said gas is exhausted from said space.

11. (Previously Presented) The apparatus according to claim 10 wherein said first electrode is grounded.

12. (Previously Presented) The apparatus according to claim 10 wherein said second electrode is located below said first electrode.

13. (Previously Presented) The apparatus according to claim 10 wherein said apparatus is a film formation apparatus.

14. (Previously Presented) The apparatus according to claim 10 wherein said gas inlet port is located in a position between the substrate and the second electrode.

15.-19. (Cancelled)

20. (Previously Presented) The plasma CVD apparatus according to claim 1 further comprising an abnormal discharge preventing plate between said exhaust means and said electrode wherein said abnormal discharge preventing plate has a plurality of openings.

21. (Previously Presented) The plasma CVD apparatus according to claim 10 further comprising an abnormal discharge preventing plate between said second electrode and

exhausting port of the chamber wherein said abnormal discharge preventing plate has a plurality of openings.

22. (New) A plasma CVD apparatus comprising:
a vacuum chamber;
an exhaust means for exhausting the gas from the vacuum chamber to an outside;
an electrode for supplying an electric energy inside the vacuum chamber;
a supporting means for supporting a substrate opposing the electrode wherein said substrate is moved in a first direction through said chamber;
an introducing port for gas, located between the electrode and the substrate wherein said gas is introduced into said chamber in a direction parallel with said first direction; and
an abnormal discharge preventing plate between said exhaust means and said electrode wherein said abnormal discharge preventing plate has a plurality of openings,
wherein a plurality of openings are located on a surface of the electrode opposing the substrate,
wherein the gas is exhausted from the plurality of openings of said electrode and the plurality of openings of said abnormal discharge preventing plate to the outside of the vacuum chamber.

23. (New) An apparatus according to claim 22, further comprising:
a transporting means for transporting continuously the substrate in said first direction.

24. (New) An apparatus according to claim 22, wherein each of the plurality of openings is circular,
wherein the plurality of openings are located on the surface of the electrode at constant intervals.

25. (New) An apparatus according to claim 22, wherein the electrode is a mesh-like plate.

26. (New) An apparatus according to claim 1 further comprising:
a second electrode opposing the first electrode for supplying the electric energy inside the vacuum chamber.

27. (New) An apparatus according to claim 6,
wherein the substrate is supported between the first and second electrodes by the supporting means.

28. (New) An apparatus according to claim 23,
wherein the transporting means includes at least one selected from the group consisting of an unwinding roll and a winding roll.

29. (New) The apparatus according to claim 22 wherein said substrate is located horizontally and has a substrate surface that is downwardly opposed to the electrode.

30. (New) An apparatus comprising:
a chamber;
a first electrode in the chamber;
a second electrode in the chamber;
a substrate holder to hold a substrate between the first and second electrode wherein said substrate is moved in a first direction through said chamber;
at least one gas inlet port to introduce a gas to a space between the substrate and the second electrode wherein said gas is introduced in a direction parallel to said first direction; and
a plurality of gas exhaust ports provided in said second electrode through which said gas is exhausted from said space; and

an abnormal discharge preventing plate between said second electrode and exhausting port of the chamber wherein said abnormal discharge preventing plate has a plurality of openings,

wherein said gas is exhausted through the plurality of openings of said abnormal discharge preventing plate.

31. (New) The apparatus according to claim 30 wherein said first electrode is grounded.

32. (New) The apparatus according to claim 30 wherein said second electrode is located below said first electrode.

33. (New) The apparatus according to claim 30 wherein said apparatus is a film formation apparatus.

34. (New) The apparatus according to claim 30 wherein said gas inlet port is located in a position between the substrate and the second electrode.